ELSEVIER

Thin Solid Films 302 (1997) 275

thin solid films

Author Index of Volume 302

Ai, C.-F. 193
Amelichev, V.A. 140
Aoyama, H. 122

Bae, K.S. 260
Barnett, S.A. 147
Barshilia, H.C. 250
Basit, N.A. 155
Bergstrom, D. 179
Blachere, J. 155
Bolse, W. 162

Carrara, S. 89
Checchetto, R. 77
Chen, C.S. 98
Chen, F. 201
Chen, G. 256
Ching, Y.-c. 231
Cho, S.W. 25
Cho, Y.S. 260
Choi, J.-W. 116
Christ, T. 214

Davazoglou, D. 204
De Caro, L. 239
Dessaux, O. 58
Dhanasekaran, R. 71
Druzhko, A.B. 231

Edelmann, A. 31

Feng, Z.C. 111
Forcht, K. 43
Friedbacher, G. 5
Fukunaga, O. 133

Geffart, F. 214
Glüsen, B. 214
Gombert, A. 43
Gong, J. 256
Gorbenko, O.Yu. 140
Gorenstein, A. 66
Gossmann, H.-J. 127
Goudmand, P. 58
Grasserbauer, M. 5
Greene, J.E. 179
Guerin, D. 201
Gusso, M. 239
Guu, Y.Y. 193

Haram, S.K. 12
Haussalo, P. 162
He, Z.D. 98
Herner, S.B. 127
Hirakuri, K.K. 5
Hong, S.Y. 260
Huang, L. 98
Hurkmans, T. 179
Hyodo, H. 133

Illgner, C. 162
Ishibashi, Y. 133
Ismat Shah, S. 201
Iwata, F. 122

Jama, C. 58
Ji, T.S. 270
Joerger, R. 43
Jones, K.S. 127

Kawaguchi, M. 122
Kazaryan, E.M. 54
Keinonen, J. 162
Kettner, A. 214
Kim, H.-w. 169
Kim, H.-Y. 17
Kim, H.K. 155
Kim, I.G. 25
Kim, J.R. 260
Köhl, M. 43
Kolodner, P. 231
Kolodzey, J. 201
Korsakov, I.E. 140
Kosjuk, L.M. 235
Krishnamoorthy, V. 127
Kshirsagar, S.T. 102
Kumbhar, A.A. 102

Lee, B.H. 25
Lee, D.-H. 116
Lee, J.-Y. 17
Lee, K.-Y. 17
Lee, K.D. 84
Lee, K.K. 111
Lee, S.-H. 25
Lévy-Clément, C. 12
Li, K. 111
Li, Y. 256
Lieb, K.P. 162
Lin, J. 111
Lin, J.F. 193
Lin, S. 256
Liu, H.-G. 223
Lokhande, C.D. 1
Losbichler, P. 179
Lourenço, A. 66
Lukashev, E.P. 231
Lüssem, G. 214

Ma, G. 256
Madan, A. 147
Mahajan, S.S. 250
Mehta, B.R. 250
Meng, G.Y. 98
Minorikawa, T. 5
Mkhoyan, K.A. 54
Münz, W.D. 179

Naman, A. 127
Neumann-Spallart, M. 12
Nicolini, C. 89
Niederdrenk, M. 162
Nishizawa, S. 133

Odynets, L.L. 235
Oechsner, H. 266
Ohashi, N. 133
Ohmukai, M. 51
Orner, B.A. 201

Paddeu, S. 89
Park, H.L. 270
Park, Y.B. 260
Patil, P.S. 1
Peng, D.K. 98
Petrov, I. 179

Ram, M.K. 89
Rebane, J.A. 140
Reif, R. 169
Rothhaar, U. 266
Rousseau, V. 58
Santhanam, K.S.V. 12
Sarkisyan, H.A. 54
Sasaki, A. 122
Sasikala, G. 71
Scarminio, J. 66
Schäfer, O. 214
Shinn, M. 147
Stümpflen, V. 214
Subramanian, C. 71
Suslov, S.G. 140

Tan, K.L. 111
Tapfer, L. 239
Tretyakov, Yu.D. 140
Trinh, T. 179
Tsukruk, V.V. 214
Tsurumi, T. 133
Tsutsumi, Y. 51
Tung, R.T. 127

Ubale, A.U. 1

Vankar, V.D. 250

Wachtel, H. 31
Wang, W.K. 108
Watt, F. 111
Webb, J.B. 111
Wee, A.T.S. 111
Wendorff, J.H. 214

Yakovlev, N.V. 140
Yamane, M. 133
Yang, K.-Z. 223
Yang, Y. 256
Yashar, P. 147
Yoon, I.T. 270
Yoon, K.H. 116
Yu, R.C. 108

Zhang, C.-R. 223
Zhang, H.-W. 223
Zhang, R.-J. 223
Zhou, Z.-H. 169
Zhu, G.-Y. 223

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ELSEVIER

Thin Solid Films 302 (1997) 276–279

thin solid films

Subject Index of Volume 302

Adhesion
The tribological characteristics of titanium nitride, titanium carbonitride and titanium carbide coatings, 193
Aluminum
Ultrasonic micromachining on Al thin film using atomic force microscopy combined quartz crystal resonator, 122
Amino acids
Electric-field and photochemical effects in D85N mutant bacteriorhodopsin substituted with 4-keto-retinal, 231
Amorphous film
Formation of Ti amorphous films deposited on liquid nitrogen-cooled substrates by ion-beam sputtering, 108
Amorphous materials
Raman scattering studies of amorphous Si_xGe_{1-x}:H alloy films produced by hot-filament assisted chemical vapour deposition technique, 102
Amourphous materials
Formation of Ti amorphous films deposited on liquid nitrogen-cooled substrates by ion-beam sputtering, 108
Annealing
Effect of annealing on physical properties of conducting poly(ortho-anisidine) Langmuir–Blodgett films, 89
The influence of hydrogen dilution ratio on the crystallization of hydrogenated amorphous silicon films prepared by plasma-enhanced chemical vapor deposition, 17
Anodic oxidation
Polarization processes in anodic oxide films, 235
Atomic force microscopy
Thin film characterization of diamond-like carbon films prepared by r.f. plasma chemical vapor deposition, 5
Ultrasonic micromachining on Al thin film using atomic force microscopy combined quartz crystal resonator, 122
Auger electron spectroscopy (AES)
A surface and interface study on the InSb/GaAs heterostructures, 111
Temperature induced dissolution of Cr_2O_3 into polycrystalline tantalum, 266
Band structure
Energy band offsets of SiGeC heterojunctions, 201
Biomaterials
Electric-field and photochemical effects in D85N mutant bacteriorhodopsin substituted with 4-keto-retinal, 231
Bismuth sulphide
Thickness dependent properties of chemically deposited Bi_2S_3 thin films, 1
Cadmium sulfide
Electrodeposition and optical characterisation of CdS thin films on ITO-coated glass, 71
Carbon
Enhancement of electrical conductivity in sulfur-doped C_{60} films, 256
On the determination of the sp^3 to sp^2 ratio in diamond-like carbon thin films, 250
Carbon nitride
Carbon nitride CN_x film deposition assisted by IR laser ablation in a cold remote nitrogen plasma, 58
Cathodic arc
The tribological characteristics of titanium nitride, titanium carbonitride and titanium carbide coatings, 193
Chemical vapor deposition (CVD)
Palladium membranes supported on porous ceramics prepared by chemical vapor deposition, 98
Chemical vapour deposition
On the determination of the sp^3 to sp^2 ratio in diamond-like carbon thin films, 250
Room temperature wafer surface cleaning by in-situ ECR (electron cyclotron resonance) hydrogen plasma for silicon homoepitaxial growth, 169
CN_x
Carbon nitride CN_x film deposition assisted by IR laser ablation in a cold remote nitrogen plasma, 58
Coatings
Formation of Ti amorphous films deposited on liquid nitrogen-cooled substrates by ion-beam sputtering, 108
Cold plasma
Carbon nitride CN_x film deposition assisted by IR laser ablation in a cold remote nitrogen plasma, 58
Conductivity
Effect of process parameters on the characteristics of indium tin oxide thin film for flat panel display application, 25
Enhancement of electrical conductivity in sulfur-doped C_{60} films, 256
Copper
Chemical bath deposition of cubic copper (I) selenide and its room temperature transformation to the orthorhombic phase, 12
Crystallization
The influence of hydrogen dilution ratio on the crystallization of hydrogenated amorphous silicon films prepared by plasma-enhanced chemical vapor deposition, 17
Depolarization
Incoherent superposition in ellipsometric measurements, 43
Deposition process
Carbon nitride CN_x film deposition assisted by IR laser ablation in a cold remote nitrogen plasma, 58
Deposition of WO_3 thin films by the sol–gel method, 84
Formation of Ti amorphous films deposited on liquid nitrogen-cooled substrates by ion-beam sputtering, 108
Temperature dependence of lead loss in r.f. magnetron sputtering of a stoichiometric $Pb(Zr,Ti)O_3$ target, 155
Depth profiling
CVD synthesis and SNMS characterization of thin films of ABO_3 perovskite-type materials ($PbTiO_3$, $La(Sr)CoO_3$, $La(Sr)MnO_3$, $LaNiO_3$), 140
Temperature induced dissolution of Cr_2O_3 into polycrystalline tantalum, 266

Elsevier Science S.A.

Deuterium
Titanium thin film deposition in a deuterium atmosphere, 77
Diamond-like carbon film
Thin film characterization of diamond-like carbon films prepared by r.f. plasma chemical vapor deposition, 5
Dielectric properties
Polarization processes in anodic oxide films, 235
Diffusion
CVD synthesis and SNMS characterization of thin films of ABO_3 perovskite-type materials ($PbTiO_3$, $La(Sr)CoO_3$, $La(Sr)MnO_3$, $LaNiO_3$), 140
Formation of ultra-shallow junctions using epitaxial $CoSi_2$ thin film as diffusion sources, 260
Temperature induced dissolution of Cr_2O_3 into polycrystalline tantalum, 266
Elastic properties
Strain fields and unit cell deformation in high-T_c superconductor heterostructures, 239
Electrical properties and measurements
Enhancement of electrical conductivity in sulfur-doped C_{60} films, 256
Temperature dependence of lead loss in r.f. magnetron sputtering of a stoichiometric $Pb(Zr,Ti)O_3$ target, 155
Thickness dependent properties of chemically deposited Bi_2S_3 thin films, 1
Electrochemistry
Chemical bath deposition of cubic copper (I) selenide and its room temperature transformation to the orthorhombic phase, 12
Electrochromism and photochromism in amorphous molybdenum oxide films, 66
Electrodeposition
Electrodeposition and optical characterisation of CdS thin films on ITO-coated glass, 71
Electronic devices
Analysis of light emitting diodes by X-ray reflectivity measurements, 214
Ellipsometry
On the determination of the sp^3 to sp^2 ratio in diamond-like carbon thin films, 250
Evaporation
Charge transfer reactions yielding conductive radical ion salt films of dicyanoquinonediimine, 31
Titanium thin film deposition in a deuterium atmosphere, 77
Fluorescence
Influence of several compounds on the fluorescence of rare earth complexes $Eu(TTA)_3Phen$ and $Sm(TTA)_3Phen$ in LB films, 223
Fourier transform infrared spectroscopy
Charge transfer reactions yielding conductive radical ion salt films of dicyanoquinonediimine, 31
Germanium
Indirect transitions caused by electron–dislocation interaction in size-quantized semiconductor film, 54
Raman scattering studies of amorphous Si_xGe_{1-x}:H alloy films produced by hot-filament assisted chemical vapour deposition technique, 102
Hall effect
Effect of process parameters on the characteristics of indium tin oxide thin film for flat panel display application, 25
Observation of the Burstein–Moss shift in heavily Te-doped $In_{0.5}Ga_{0.5}P$ layers grown by liquid phase epitaxy, 270
Heterostructures
Energy band offsets of SiGeC heterojunctions, 201
Structural changes in ZnO/NiO artificial superlattices made by ion beam sputtering, 133
Hydrogen
Palladium membranes supported on porous ceramics prepared by chemical vapor deposition, 98
Room temperature wafer surface cleaning by in-situ ECR (electron cyclotron resonance) hydrogen plasma for silicon homoepitaxial growth, 169
The influence of hydrogen dilution ratio on the crystallization of hydrogenated amorphous silicon films prepared by plasma-enhanced chemical vapor deposition, 17
Incoherent superposition
Incoherent superposition in ellipsometric measurements, 43
Indium antimonide
A surface and interface study on the InSb/GaAs heterostructures, 111
Indium oxide
Effect of process parameters on the characteristics of indium tin oxide thin film for flat panel display application, 25
Infrared spectroscopy
Charge transfer reactions yielding conductive radical ion salt films of dicyanoquinonediimine, 31
Thin film characterization of diamond-like carbon films prepared by r.f. plasma chemical vapor deposition, 5
Interfaces
Studies of Na-irradiated Ni/Si bilayers: Na migration and NiSi formation, 162
Ion-beam sputtering
Formation of Ti amorphous films deposited on liquid nitrogen-cooled substrates by ion-beam sputtering, 108
Ion bombardment
Ion-assisted growth of $Ti_{1-x}Al_xN/Ti_{1-y}Nb_yN$ multilayers by combined cathodic-arc/magnetron-sputter deposition, 179
Studies of Na-irradiated Ni/Si bilayers: Na migration and NiSi formation, 162
Ion implantation
Formation of ultra-shallow junctions using epitaxial $CoSi_2$ thin film as diffusion sources, 260
Langmuir–Blodgett films
Effect of annealing on physical properties of conducting poly(ortho-anisidine) Langmuir–Blodgett films, 89
Influence of several compounds on the fluorescence of rare earth complexes $Eu(TTA)_3Phen$ and $Sm(TTA)_3Phen$ in LB films, 223
Lanthanides
Influence of several compounds on the fluorescence of rare earth complexes $Eu(TTA)_3Phen$ and $Sm(TTA)_3Phen$ in LB films, 223
Laser ablation
Carbon nitride CN_x film deposition assisted by IR laser ablation in a cold remote nitrogen plasma, 58
Liquid nitrogen-cooled
Formation of Ti amorphous films deposited on liquid nitrogen-cooled substrates by ion-beam sputtering, 108
Liquid phase epitaxy
Observation of the Burstein–Moss shift in heavily Te-doped $In_{0.5}Ga_{0.5}P$ layers grown by liquid phase epitaxy, 270
Luminescence
Characterization of porous silicon by means of photoacoustic spectroscopy, 51
Observation of the Burstein–Moss shift in heavily Te-doped $In_{0.5}Ga_{0.5}P$ layers grown by liquid phase epitaxy, 270
Molybdenum oxide
Electrochromism and photochromism in amorphous molybdenum oxide films, 66
Nanostructures
Characterization of porous silicon by means of photoacoustic spectroscopy, 51
Thickness dependent properties of chemically deposited Bi_2S_3 thin films, 1
Nickel oxide
Structural changes in ZnO/NiO artificial superlattices made by ion beam sputtering, 133

Nitrides
An X-ray diffraction study of epitaxial TiN/NbN superlattices, 147
Ion-assisted growth of $Ti_{1-x}Al_xN/Ti_{1-y}Nb_yN$ multilayers by combined cathodic-arc/magnetron-sputter deposition, 179
Non-stoichiometry
Characteristics of ZnO thin films deposited onto Al/Si substrates by r.f. magnetron sputtering, 116
Nuclear reaction analysis (NRA)
Studies of Na-irradiated Ni/Si bilayers: Na migration and NiSi formation, 162
Optical coatings
Optical properties of SnO_2 thin films grown by atmospheric pressure chemical vapour deposition oxidizing $SnCl_4$, 204
Optical properties
Deposition of WO_3 thin films by the sol–gel method, 84
Electrodeposition and optical characterisation of CdS thin films on ITO-coated glass, 71
Indirect transitions caused by electron–dislocation interaction in size-quantized semiconductor film, 54
On the determination of the sp^3 to sp^2 ratio in diamond-like carbon thin films, 250
Optical properties of SnO_2 thin films grown by atmospheric pressure chemical vapour deposition oxidizing $SnCl_4$, 204
Thickness dependent properties of chemically deposited Bi_2S_3 thin films, 1
Optical spectroscopy
Characterization of porous silicon by means of photoacoustic spectroscopy, 51
Electric-field and photochemical effects in D85N mutant bacteriorhodopsin substituted with 4-keto-retinal, 231
Optical properties of SnO_2 thin films grown by atmospheric pressure chemical vapour deposition oxidizing $SnCl_4$, 204
Organic substances
Charge transfer reactions yielding conductive radical ion salt films of dicyanoquinonediimine, 31
Organometallic vapour deposition
CVD synthesis and SNMS characterization of thin films of ABO_3 perovskite-type materials ($PbTiO_3$, La(Sr)CoO_3, La(Sr)MnO_3, $LaNiO_3$), 140
Orientation
Characteristics of ZnO thin films deposited onto Al/Si substrates by r.f. magnetron sputtering, 116
Oxides
CVD synthesis and SNMS characterization of thin films of ABO_3 perovskite-type materials ($PbTiO_3$, La(Sr)CoO_3, La(Sr)MnO_3, $LaNiO_3$), 140
Polarization processes in anodic oxide films, 235
Temperature induced dissolution of Cr_2O_3 into polycrystalline tantalum, 266
Palladium
Palladium membranes supported on porous ceramics prepared by chemical vapor deposition, 98
Phase transitions
Chemical bath deposition of cubic copper (I) selenide and its room temperature transformation to the orthorhombic phase, 12
Plasma processing and deposition
Room temperature wafer surface cleaning by in-situ ECR (electron cyclotron resonance) hydrogen plasma for silicon homoepitaxial growth, 169
Polyaniline
Effect of annealing on physical properties of conducting poly(ortho-anisidine) Langmuir–Blodgett films, 89
Polymers
Analysis of light emitting diodes by X-ray reflectivity measurements, 214
Poly(ortho-anisidine)
Effect of annealing on physical properties of conducting poly(ortho-anisidine) Langmuir–Blodgett films, 89
Quantum effects
Indirect transitions caused by electron–dislocation interaction in size-quantized semiconductor film, 54
Quartz
Ultrasonic micromachining on Al thin film using atomic force microscopy combined quartz crystal resonator, 122
Raman scattering
Raman scattering studies of amorphous Si_xGe_{1-x}:H alloy films produced by hot-filament assisted chemical vapour deposition technique, 102
Resistivity
Characteristics of ZnO thin films deposited onto Al/Si substrates by r.f. magnetron sputtering, 116
R.f. magnetron sputtering
Characteristics of ZnO thin films deposited onto Al/Si substrates by r.f. magnetron sputtering, 116
Rutherford backscattering spectroscopy
A surface and interface study on the InSb/GaAs heterostructures, 111
Deposition of WO_3 thin films by the sol–gel method, 84
Studies of Na-irradiated Ni/Si bilayers: Na migration and NiSi formation, 162
Secondary ion mass spectrometry (SIMS)
Formation of ultra-shallow junctions using epitaxial $CoSi_2$ thin film as diffusion sources, 260
Selenides
Chemical bath deposition of cubic copper (I) selenide and its room temperature transformation to the orthorhombic phase, 12
Semiconductors
Energy band offsets of SiGeC heterojunctions, 201
Indirect transitions caused by electron–dislocation interaction in size-quantized semiconductor film, 54
Observation of the Burstein–Moss shift in heavily Te-doped $In_{0.5}Ga_{0.5}P$ layers grown by liquid phase epitaxy, 270
Silicides
Formation of ultra-shallow junctions using epitaxial $CoSi_2$ thin film as diffusion sources, 260
Morphology of $TiSi_2$ films on Si formed from co-deposited Ti and Si, 127
Silicon
Characterization of porous silicon by means of photoacoustic spectroscopy, 51
Raman scattering studies of amorphous Si_xGe_{1-x}:H alloy films produced by hot-filament assisted chemical vapour deposition technique, 102
The influence of hydrogen dilution ratio on the crystallization of hydrogenated amorphous silicon films prepared by plasma-enhanced chemical vapor deposition, 17
Spectroscopic ellipsometry
Incoherent superposition in ellipsometric measurements, 43
Sputtering
Effect of process parameters on the characteristics of indium tin oxide thin film for flat panel display application, 25
Electrochromism and photochromism in amorphous molybdenum oxide films, 66
Ion-assisted growth of $Ti_{1-x}Al_xN/Ti_{1-y}Nb_yN$ multilayers by combined cathodic-arc/magnetron-sputter deposition, 179
Temperature dependence of lead loss in r.f. magnetron sputtering of a stoichiometric $Pb(Zr,Ti)O_3$ target, 155
Structural properties
Electrodeposition and optical characterisation of CdS thin films on ITO-coated glass, 71
Strain fields and unit cell deformation in high-T_c superconductor heterostructures, 239
Sulphur
Enhancement of electrical conductivity in sulfur-doped C_{60} films, 256
Superconductivity
Strain fields and unit cell deformation in high-T_c superconductor heterostructures, 239

Superlattices
An X-ray diffraction study of epitaxial TiN/NbN superlattices, 147
Strain fields and unit cell deformation in high-T_c superconductor heterostructures, 239
Structural changes in ZnO/NiO artificial superlattices made by ion beam sputtering, 133
Surface morphology
Thin film characterization of diamond-like carbon films prepared by r.f. plasma chemical vapor deposition, 5
Surface structure
Analysis of light emitting diodes by X-ray reflectivity measurements, 214
Tin oxide
Optical properties of SnO_2 thin films grown by atmospheric pressure chemical vapour deposition oxidizing $SnCl_4$, 204
Titanium
Formation of Ti amorphous films deposited on liquid nitrogen-cooled substrates by ion-beam sputtering, 108
Titanium thin film deposition in a deuterium atmosphere, 77
Titanium carbonitride
The tribological characteristics of titanium nitride, titanium carbonitride and titanium carbide coatings, 193
Transmission electron microscopy (TEM)
Morphology of $TiSi_2$ films on Si formed from co-deposited Ti and Si, 127
Transmission electron microscopy
Room temperature wafer surface cleaning by in-situ ECR (electron cyclotron resonance) hydrogen plasma for silicon homoepitaxial growth, 169
Transmission ellipsometry
Incoherent superposition in ellipsometric measurements, 43
Tribology
Ultrasonic micromachining on Al thin film using atomic force microscopy combined quartz crystal resonator, 122
Tungsten oxide
Deposition of WO_3 thin films by the sol–gel method, 84
Wear
The tribological characteristics of titanium nitride, titanium carbonitride and titanium carbide coatings, 193
X-ray diffraction
A surface and interface study on the InSb/GaAs heterostructures, 111
An X-ray diffraction study of epitaxial TiN/NbN superlattices, 147
Analysis of light emitting diodes by X-ray reflectivity measurements, 214
Influence of several compounds on the fluorescence of rare earth complexes $Eu(TTA)_3Phen$ and $Sm(TTA)_3Phen$ in LB films, 223
Temperature dependence of lead loss in r.f. magnetron sputtering of a stoichiometric $Pb(Zr,Ti)O_3$ target, 155
Titanium thin film deposition in a deuterium atmosphere, 77
X–ray photoelectron spectroscopy (XPS)
Energy band offsets of SiGeC heterojunctions, 201
Zinc oxide
Structural changes in ZnO/NiO artificial superlattices made by ion beam sputtering, 133
ZnO thin film
Characteristics of ZnO thin films deposited onto Al/Si substrates by r.f. magnetron sputtering, 116